

Product Data Sheet

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PRODUCT #: N5100

CIRCUTEK PD-776

Liquid Pre-Dip

DESCRIPTION: Pre-dip solution used in conjunction with *CIRCUTEK C-777* activator in catalyzing the substrate for subsequent electroless copper deposition. *CIRCUTEK PD-776* replaces the hydrochloric acid and water normally used in the step prior to the activator and in the activator solution itself.

BENEFITS:

- **Convenient, ready to use solution with economical, concentrated dry replenisher**
- **More consistent results than with “home-brew” acid pre-dip**
- **Protects expensive catalyst bath**

INSTRUCTIONS:

CIRCUTEK PD-776 solution is used full strength as supplied when used as a pre-dip solution preceding *CIRCUTEK C-777* Activator.

Operating Parameters:

Time: 2 - 7 minutes
Temperature: 60 - 95°F
Agitation: Work load

Replenishment:

A dynel anode bag filled with *CIRCUTEK PD-776S* salt should be placed in the pre-dip solution and kept filled. This will ensure that the components present in the solution remain constant during operation.

If additions are necessary to maintain solution level, fresh *CIRCUTEK PD-776* solution should be used. Do not add water to maintain solution level.

Solution Control:

Using a pH meter standardized at pH 4.0, measure the pH of the pre-dip solution. The pH of this solution should be 0.5 or less. If it is not, the pH should be reduced via additions of reagent grade hydrochloric acid until within the desired range.

CAUTIONS:

Acidic solution; avoid eye, skin and oral contact. Wear protective goggles and clothing when handling this material. Flush exposed area with water. In case of injury seek medical attention.

This product should be used only for its intended purpose. The information stated above is based on our laboratory tests and experience, and is accurate to the best of our knowledge. Since actual use is beyond our control, the recommendations or suggestions are made without warranty, expressed or implied.